



# STRUCTURAL ANALYSIS OF TSVs

**HUGO BENDER**

**CHRIS DRIJBOOMS, PATRICIA VAN MARCKE,  
JEF GEYPEN, OLIVIER RICHARD, PAOLA FAVIA**

EFUG2010  
Gaeta, 11 October 2010



# OUTLINE

Introduction : 3D device stacking

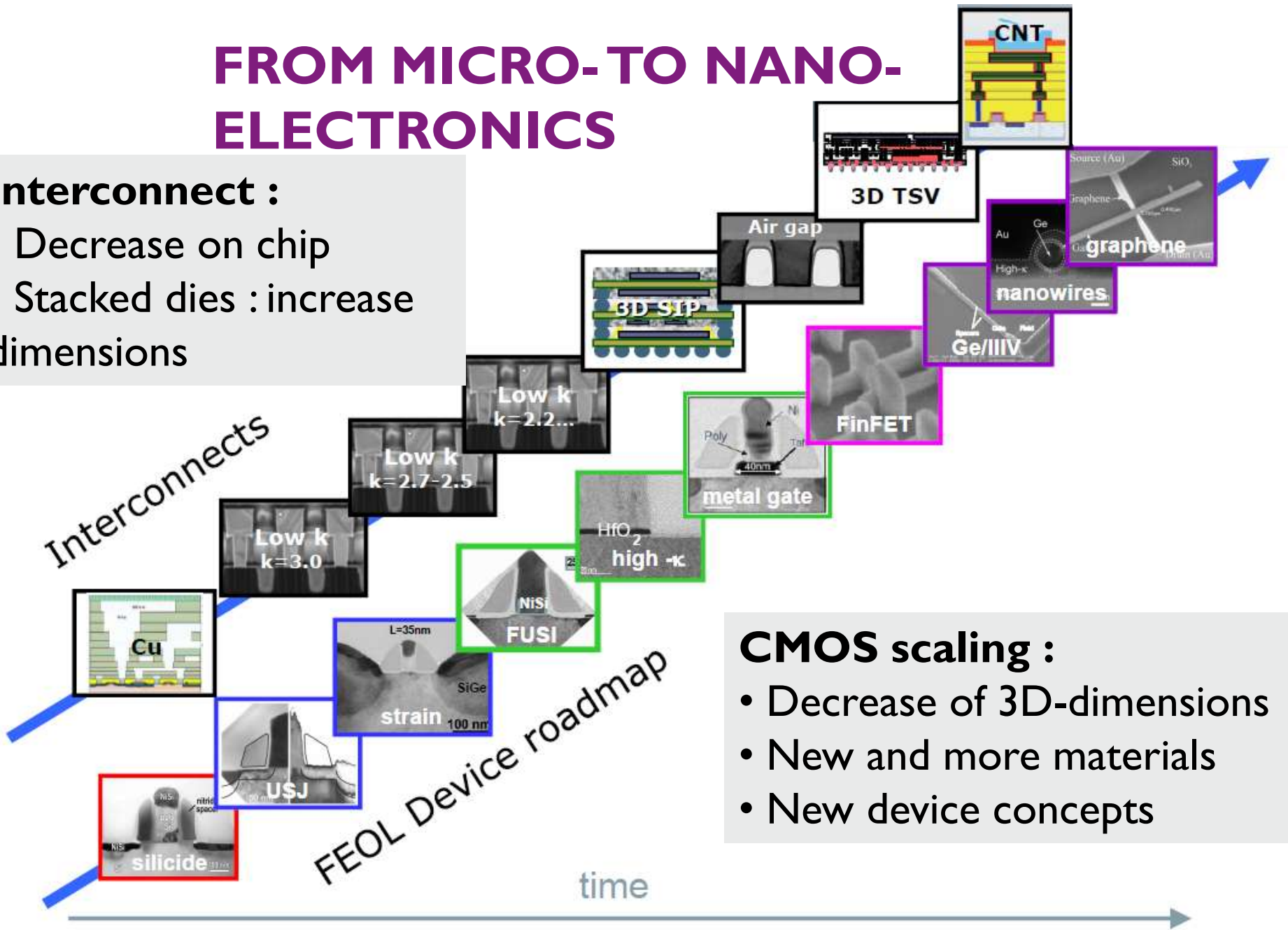
FIB analysis

- ▶ Polish and FIB/SEM
- ▶ Standard FIB/SEM
- ▶ Alternative configurations for FIB/SEM
  
- ▶ Slice&view and 3D volume reconstruction

# FROM MICRO-TO NANO-ELECTRONICS

**Interconnect :**

- Decrease on chip
- Stacked dies : increase dimensions



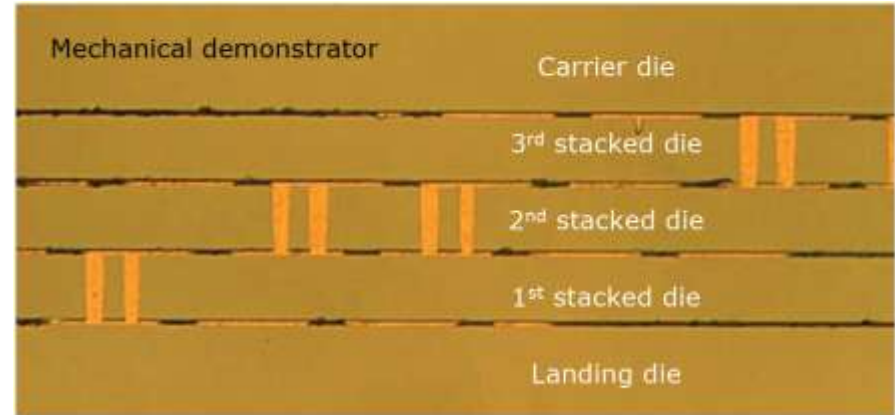
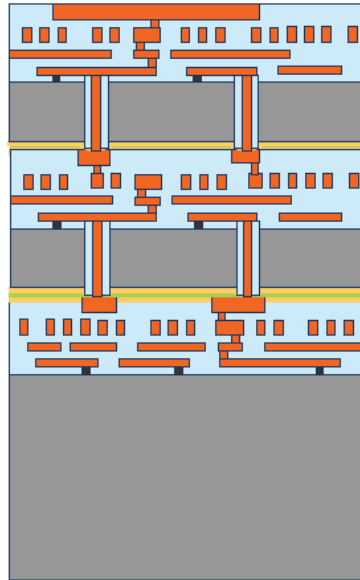
**CMOS scaling :**

- Decrease of 3D-dimensions
- New and more materials
- New device concepts

# STACKED DEVICES

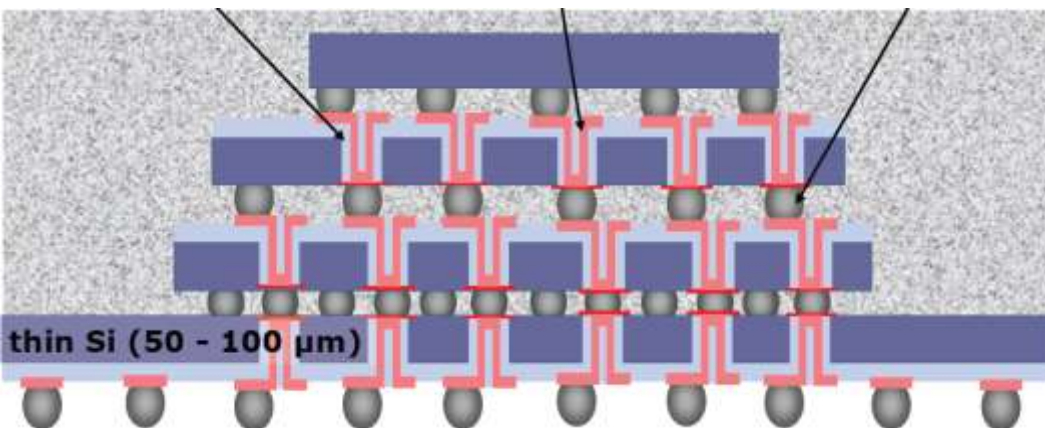
## 3D-Stacked IC

Si : 50-100  $\mu\text{m}$

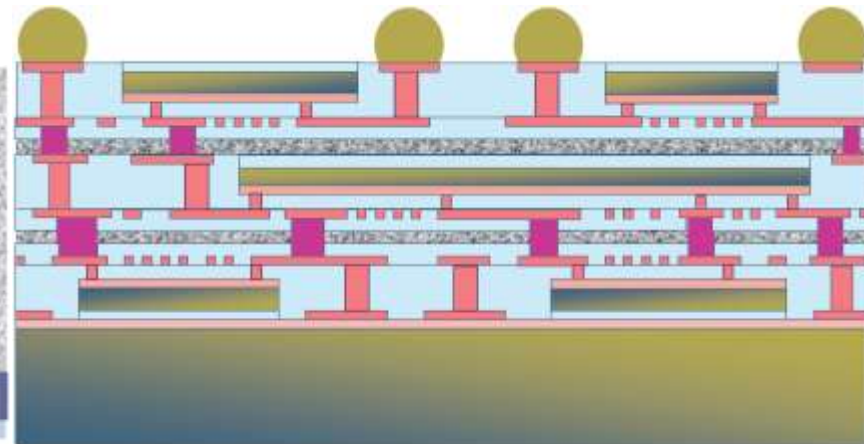


## 3D-WaferLevelPackaging

Through silicon via + microbumps

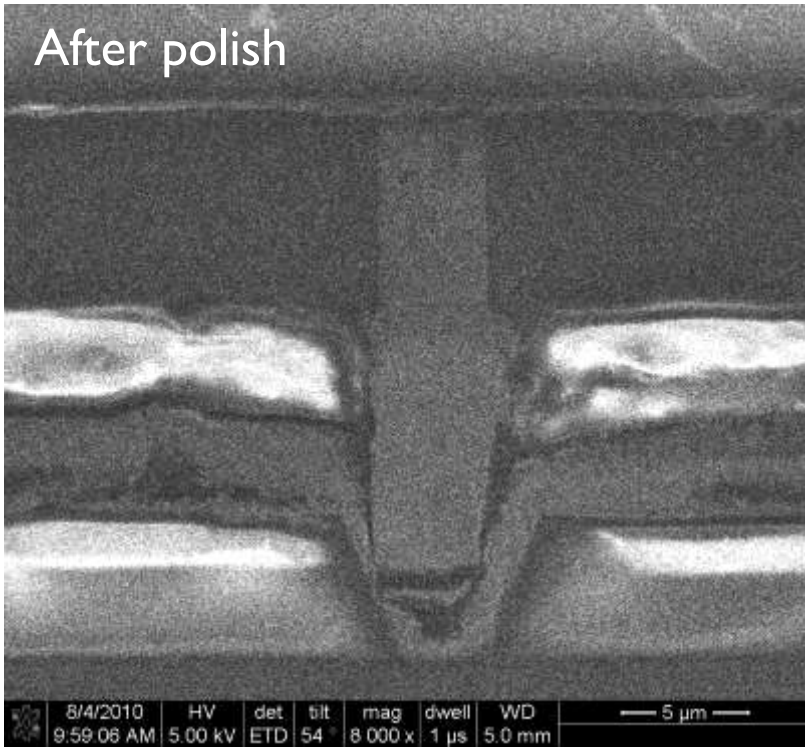


## Embedded dies



# POLISH AND FIB/SEM

After polish



epoxy

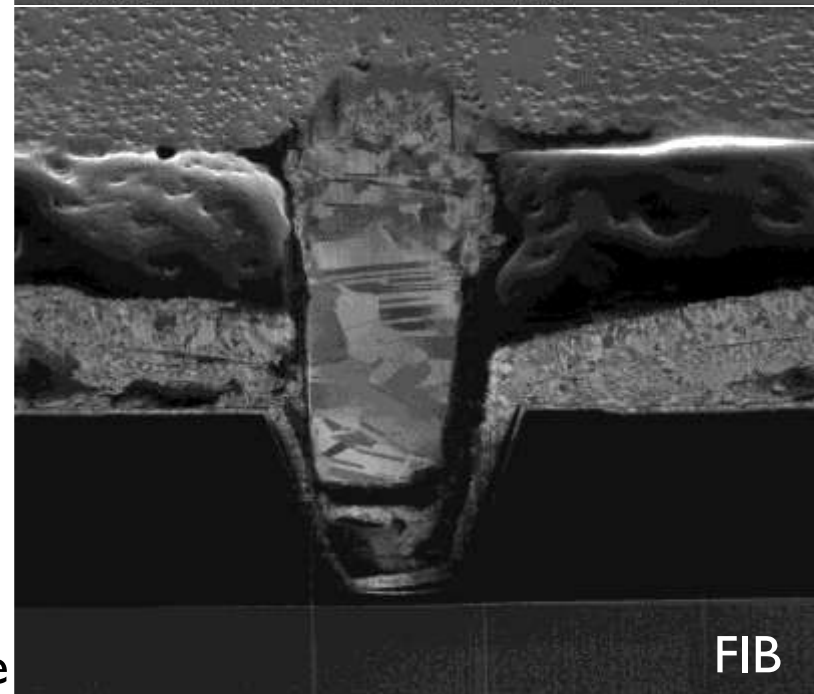
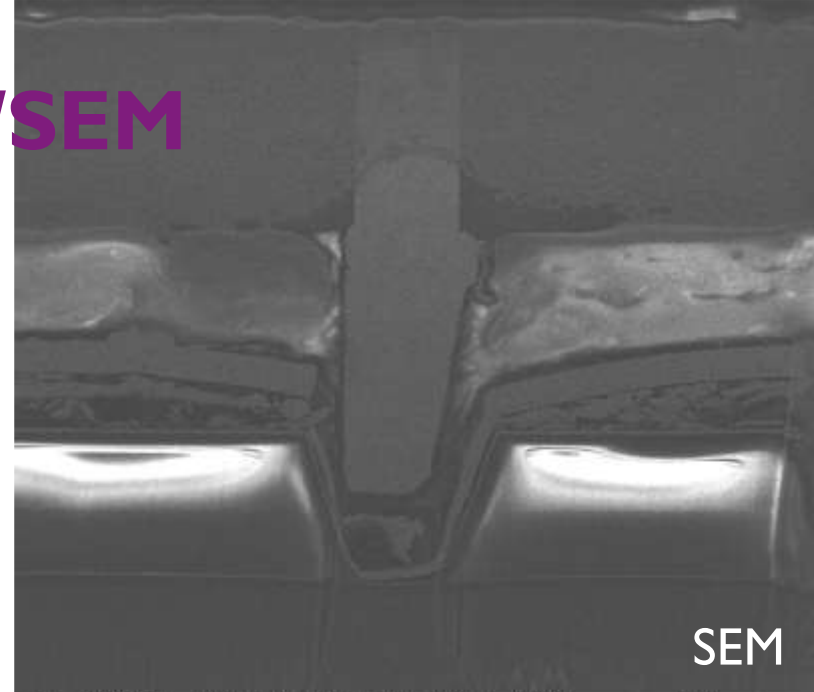
Si

epoxy

polished face

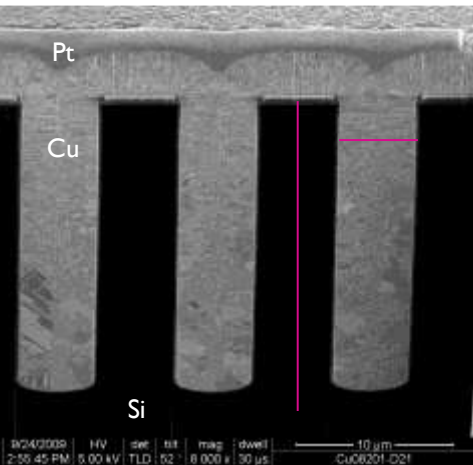
Problems :

- epoxy above : thickness and charging
- polished face not vertical
- position through the TSV unclear
- no FIB slicing through the full structure possible



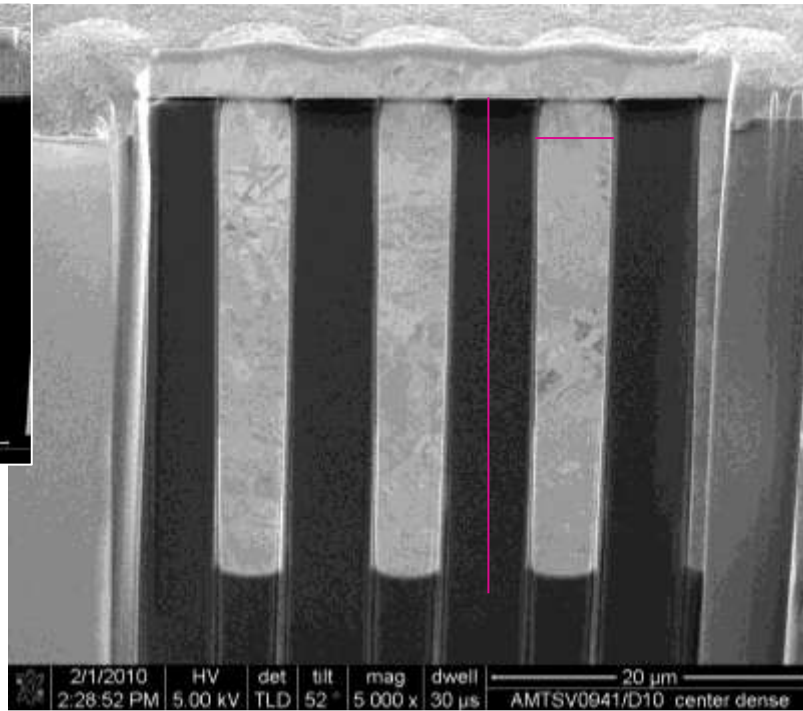
# 3D-SIC – THROUGH SILICON VIAS (TSV)

5x25  $\mu\text{m}$

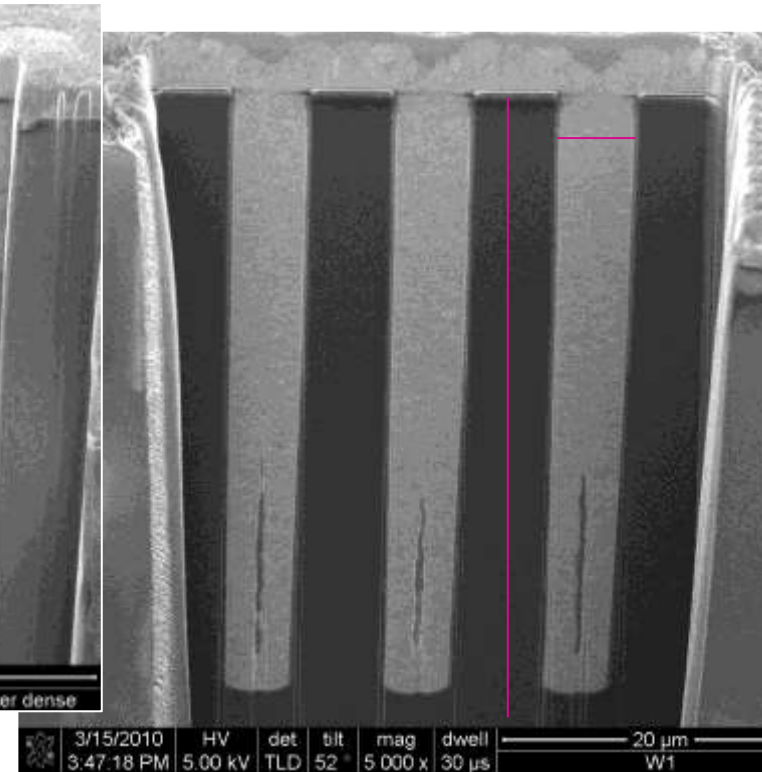


FIB/SEM

5x40  $\mu\text{m}$



5x50  $\mu\text{m}$



Interests :

- **Cu filling (small voids)**
- **grain size**
- barrier
- oxide liner

Analysis challenges :

- **dimensions vs required resolution**
- depth of focus & contrast at bottom
- 3D analysis
- curtaining
- **analysis time**

# TSV - IMAGING MODE

Voids

Grain size  
Oxide liner

SEM

FIB

Pt

Cu

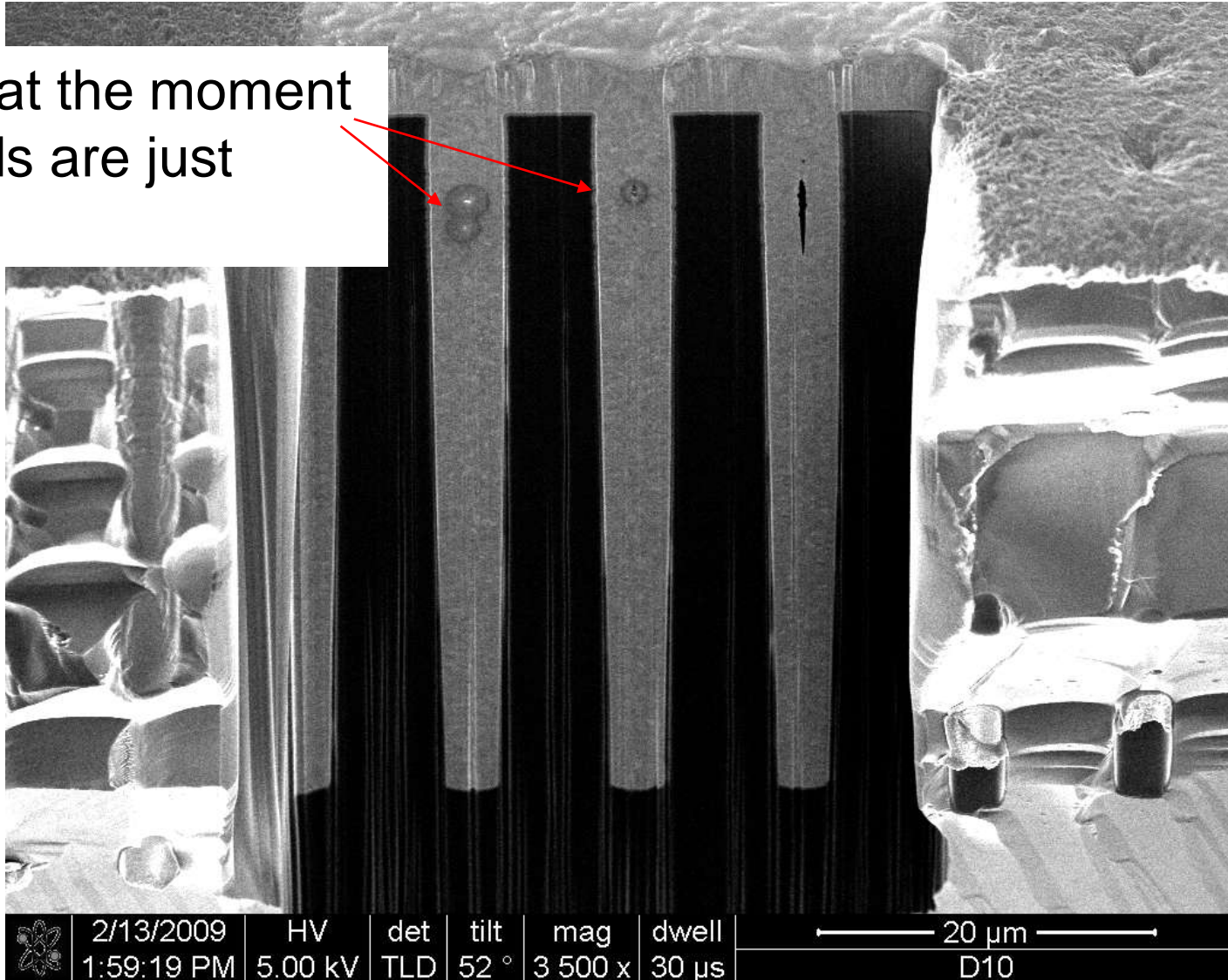
SiO<sub>2</sub>

Si

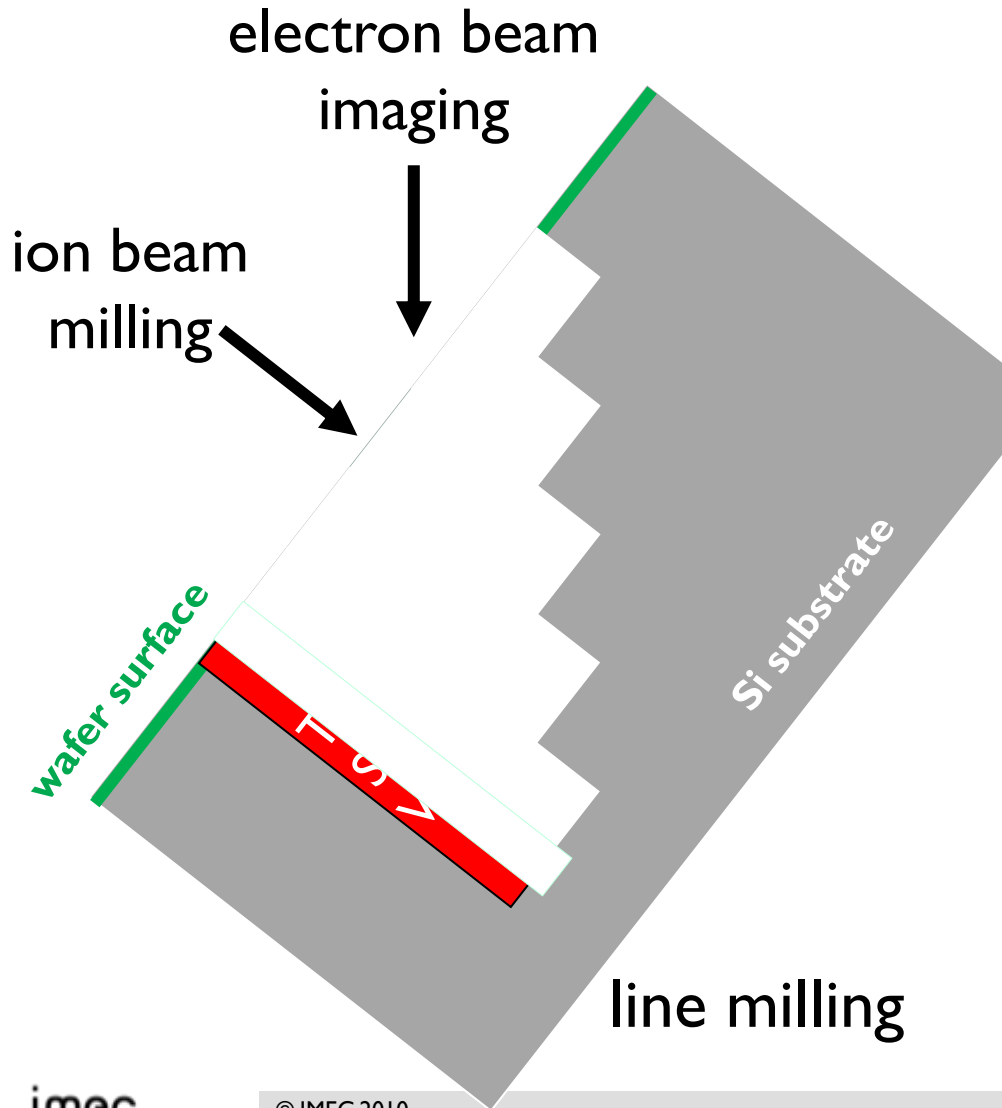
ime

# CHEMICALS IN VOIDS

“liquid” at the moment  
the voids are just  
opened



# STANDARD FIB PROCEDURE



TSV : height  $h$ , diameter  $\Phi$

milling strategy :

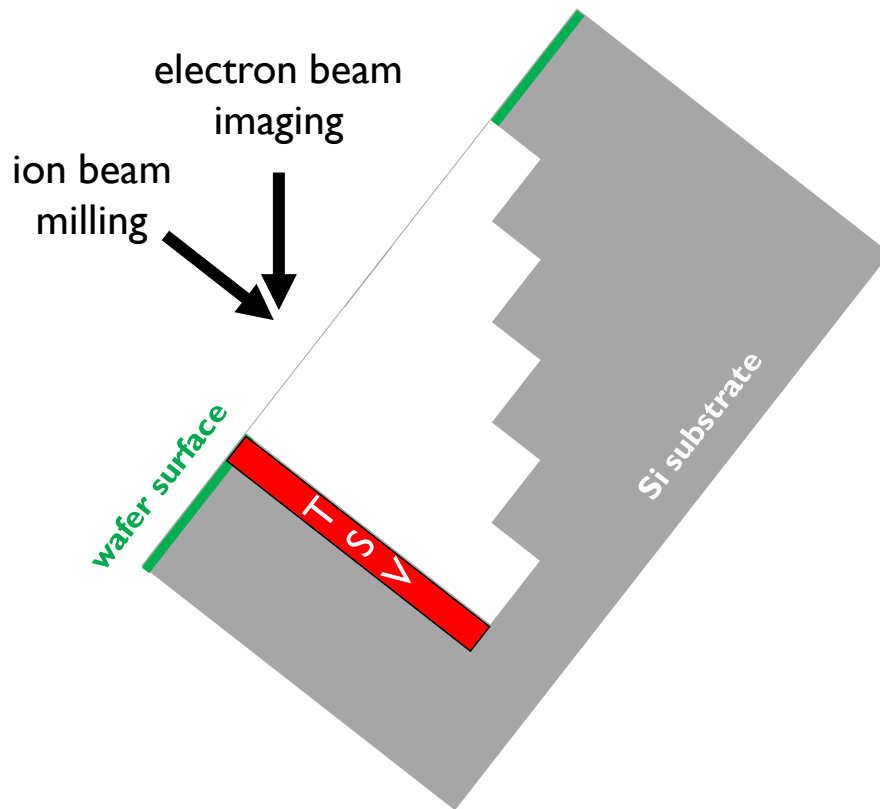
- stair case with high beam current

$$volume = \frac{d^2 w}{2 \tan(38^\circ)}$$

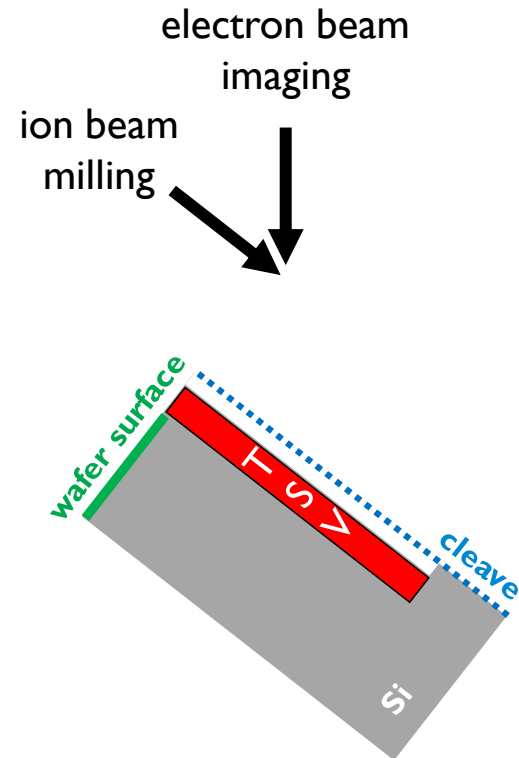
- clean : line milling with lower beam current “slice and view”

# ALTERNATIVE MILLING PROCEDURES

standard

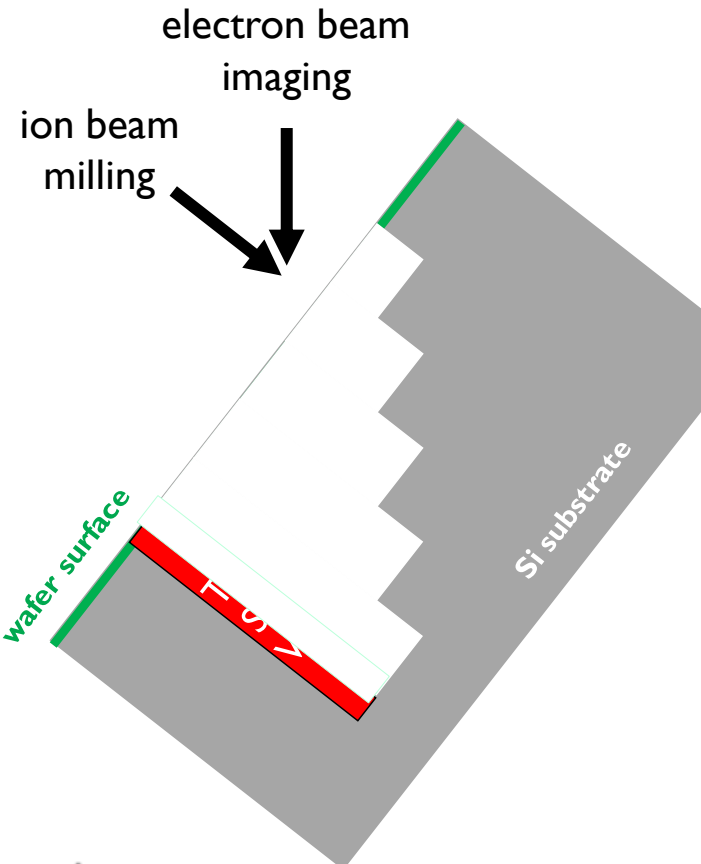


cleave  
mill sidewall

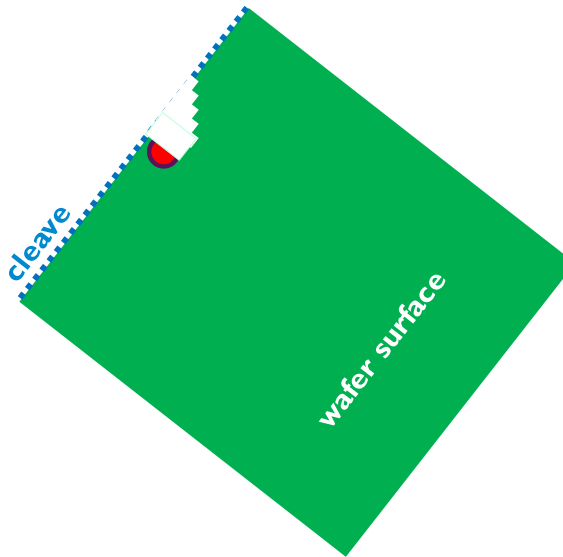


# ALTERNATIVE MILLING PROCEDURES

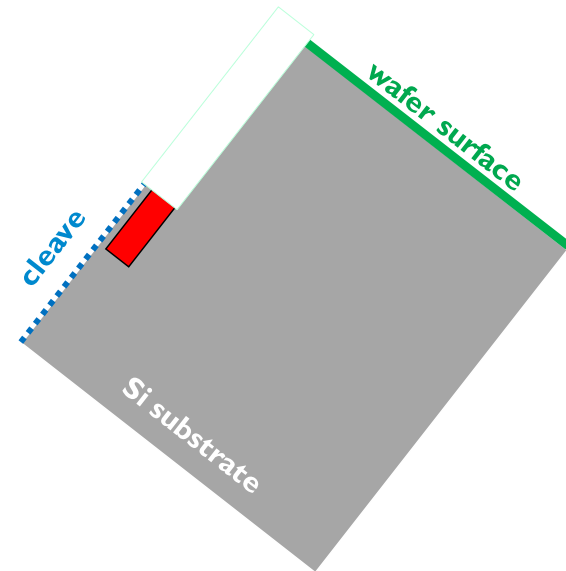
standard



cleave  
mount on edge  
mill classical way

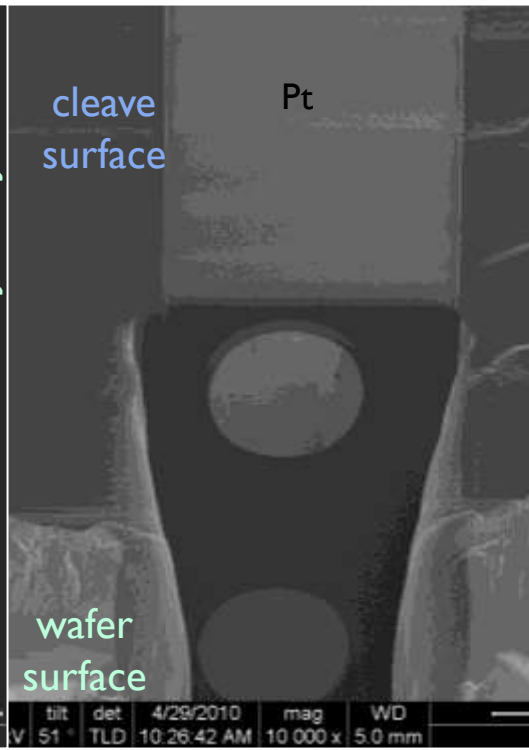
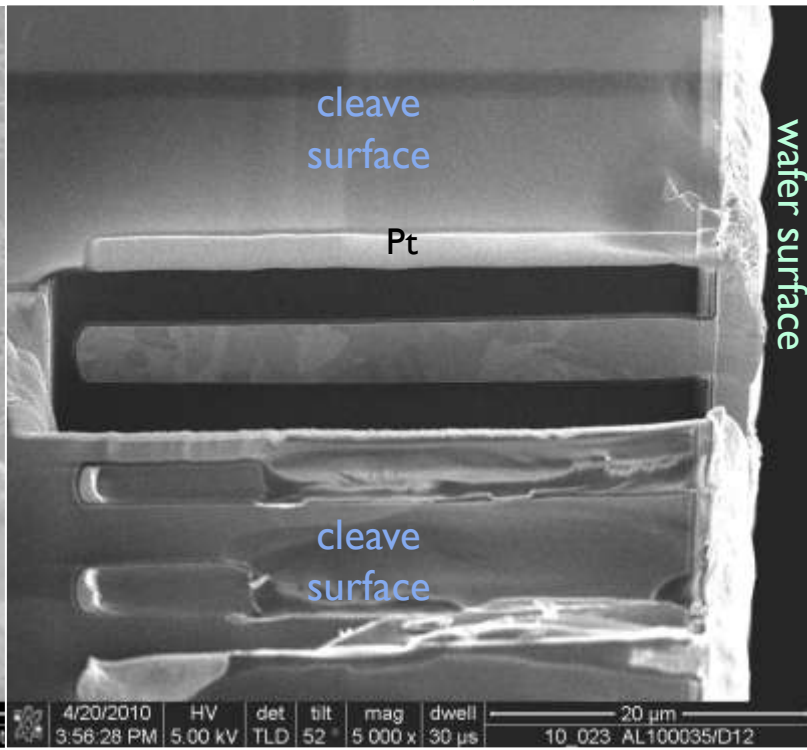
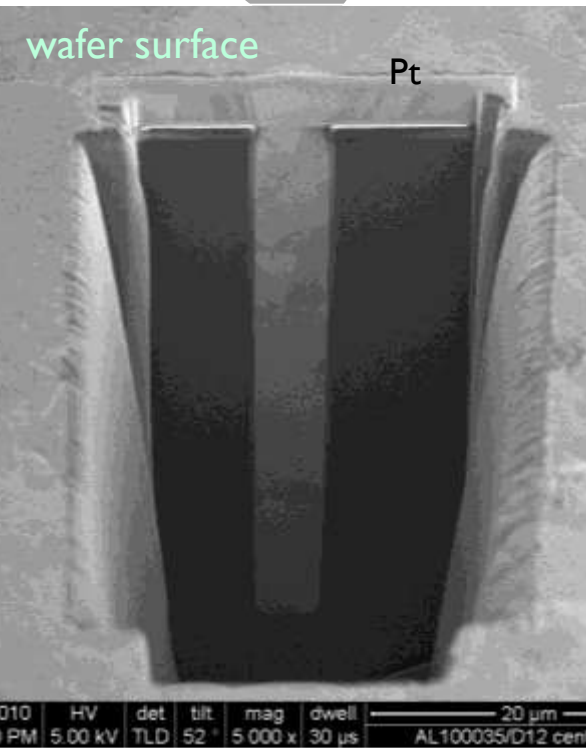
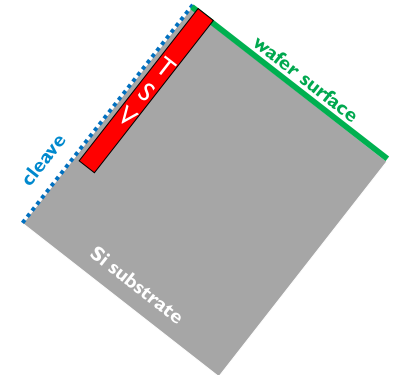
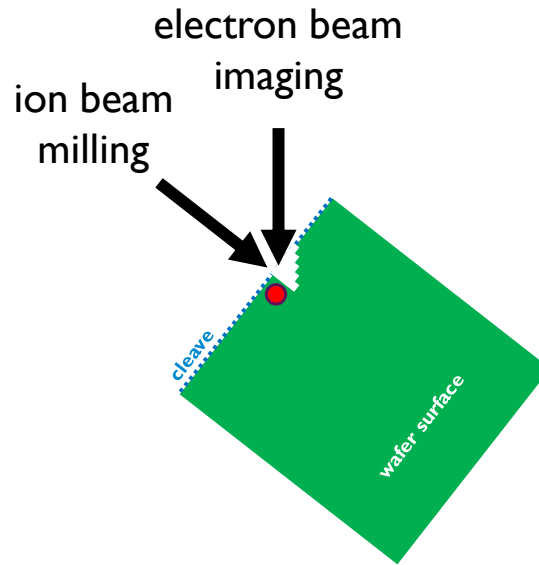
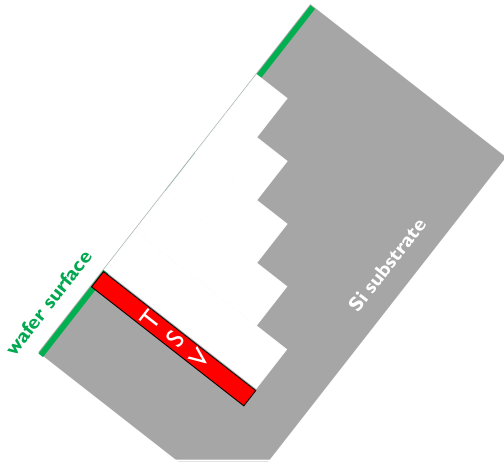


cleave  
mount on edge  
only clean mill

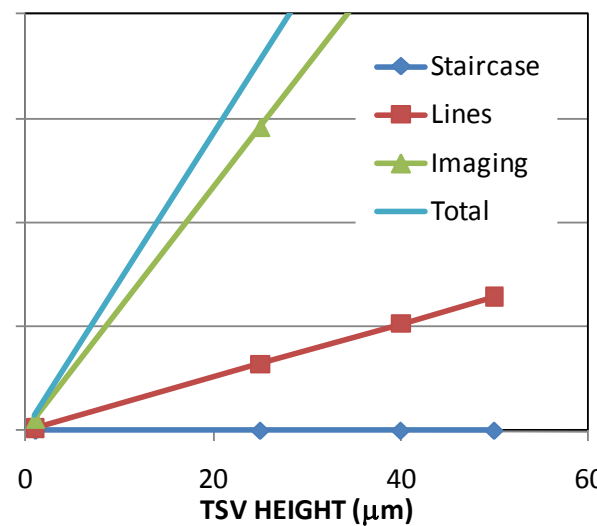
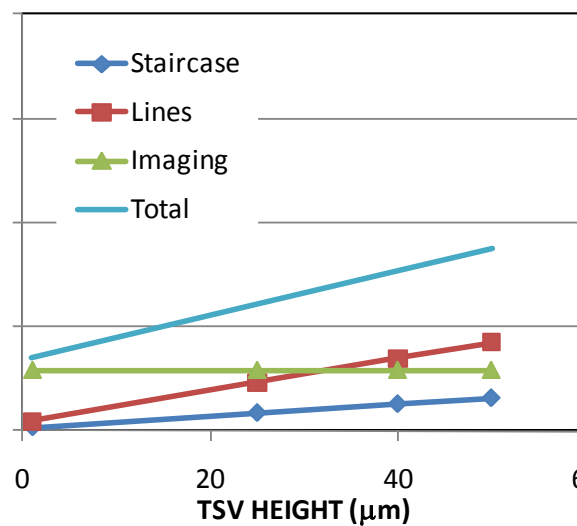
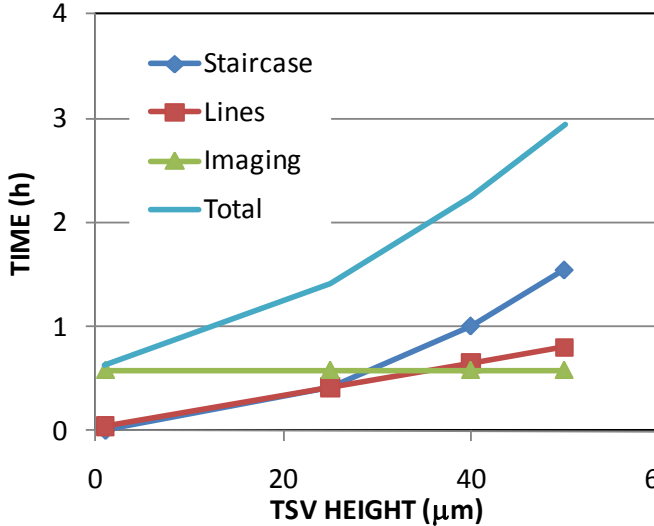
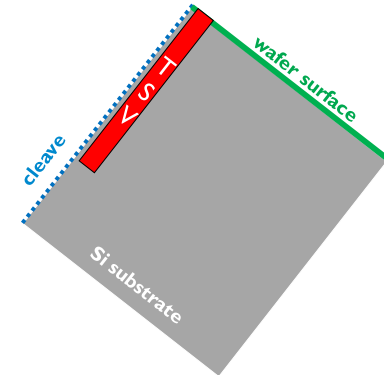
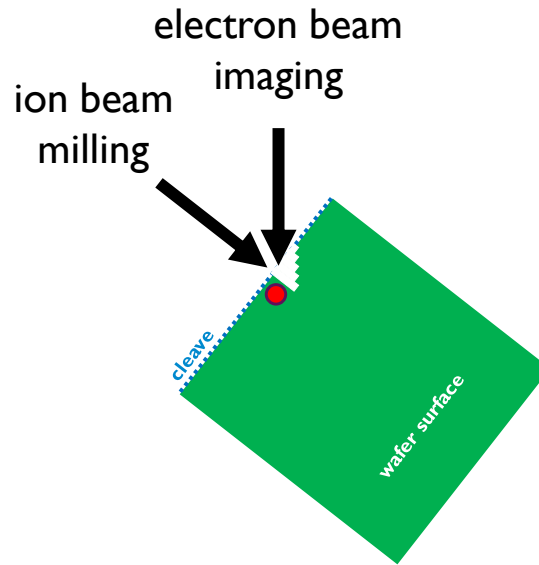
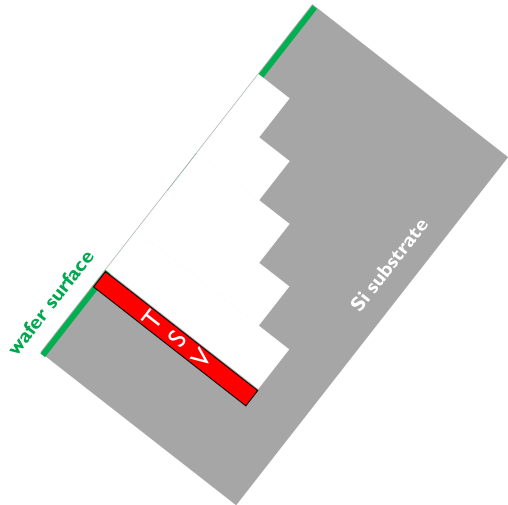


line milling

# TSV



# TSV

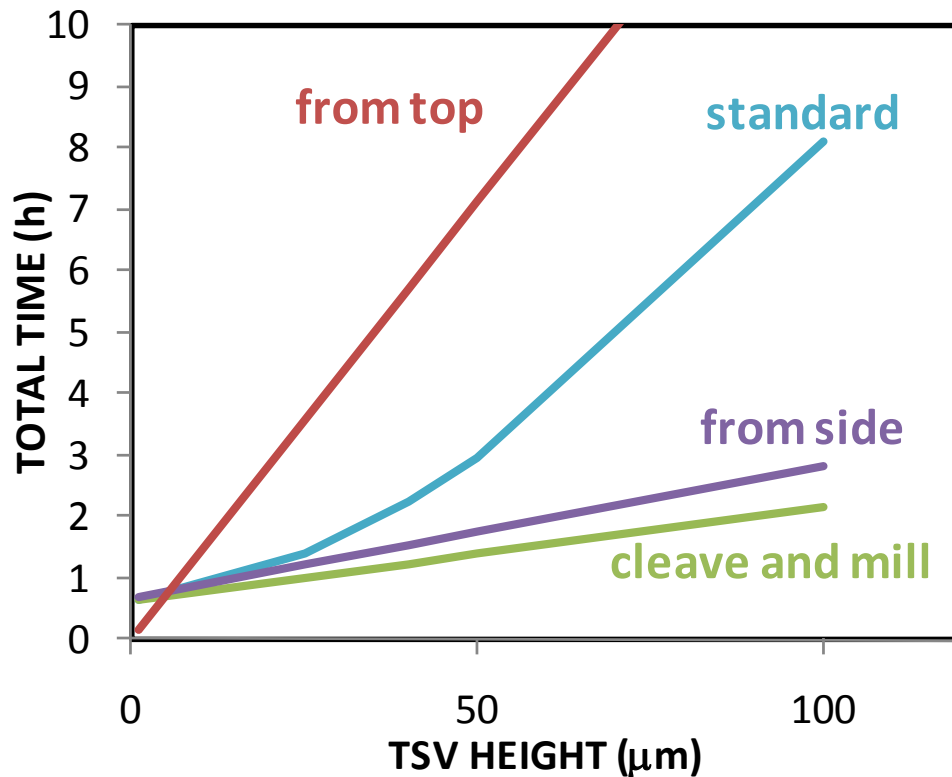
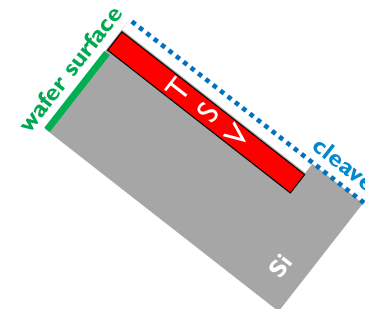
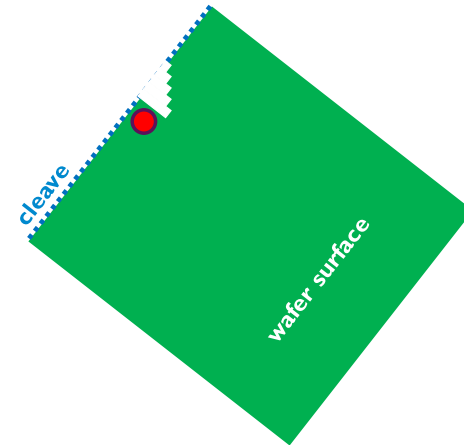
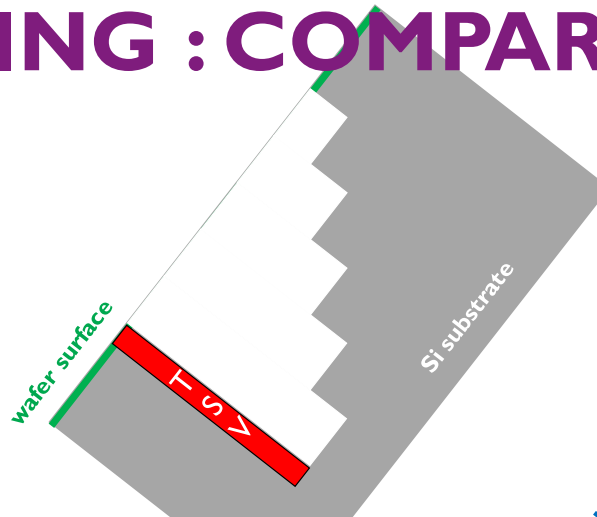
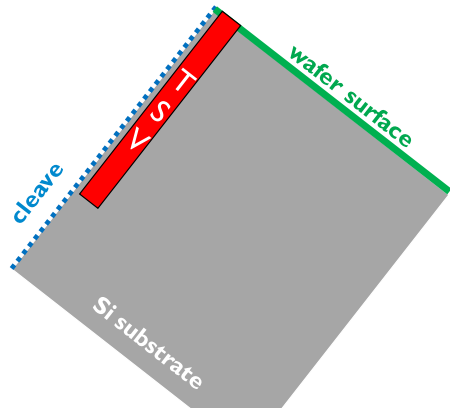


Assuming :  
 $d = h + 2\mu\text{m}$  for standard and cleave and mill ;  $d = \phi + 5\mu\text{m}$  for mount on edge  
 $w = \phi + 5\mu\text{m}$  or  $h + 5\mu\text{m}$  for from the side

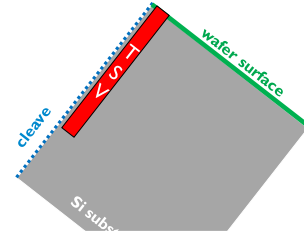
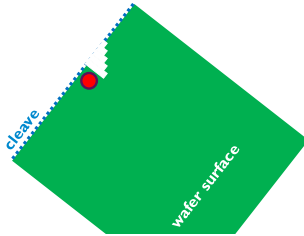
Staircase with 21 nA, slices with 2.7 nA double mill rate starting 1μm before and milling till end

Imaging at 30 μs/pixel = 0.5 min, 0.2 min switching e-<math>\rightarrow</math>ion

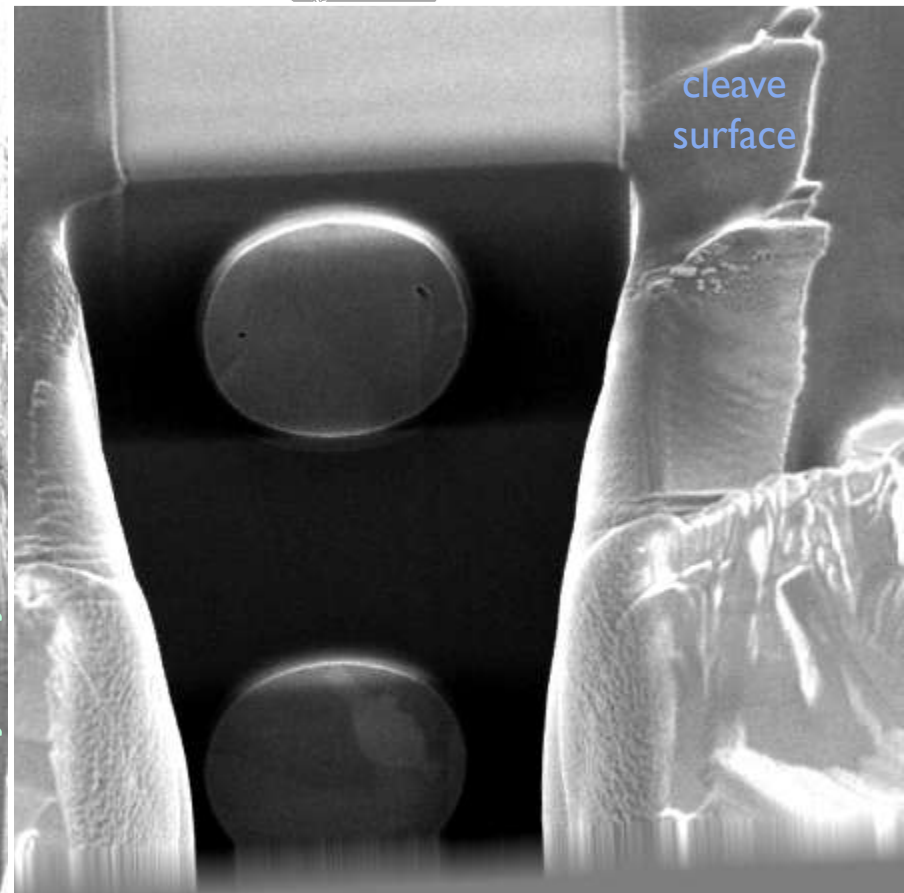
# TSV MILLING : COMPARISON



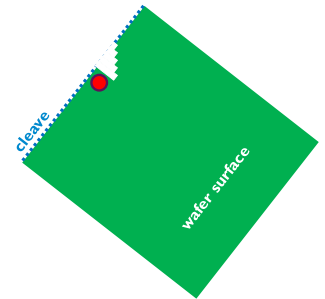
# 3D FIB SLICE & VIEW



Results of manual slice&view !

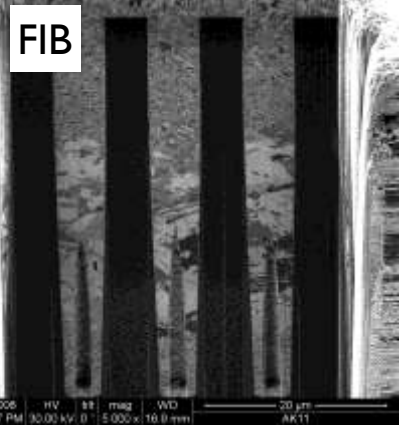
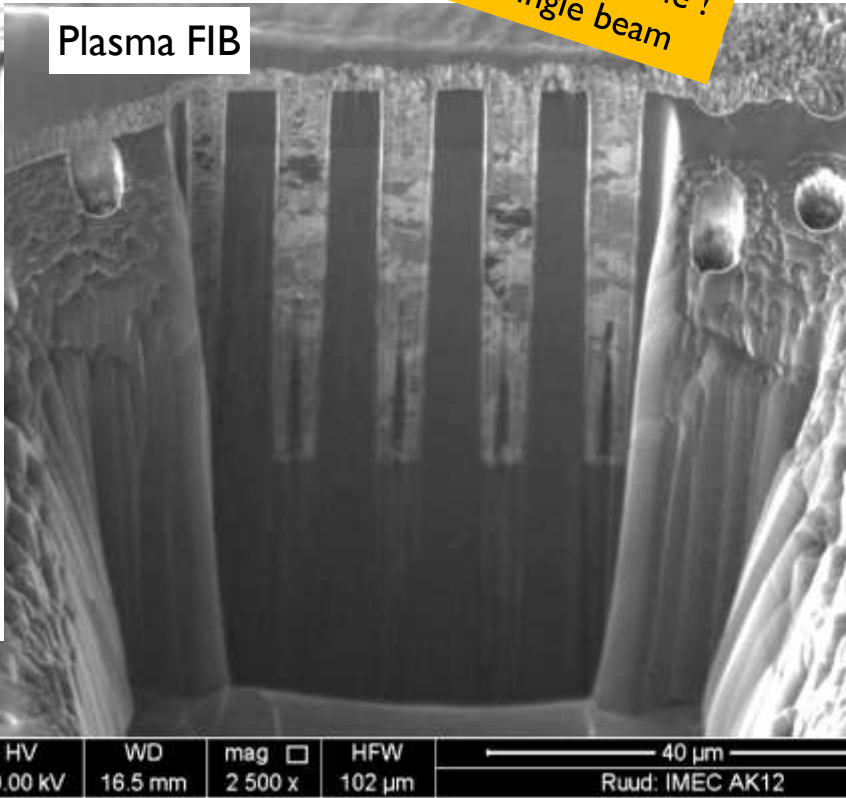
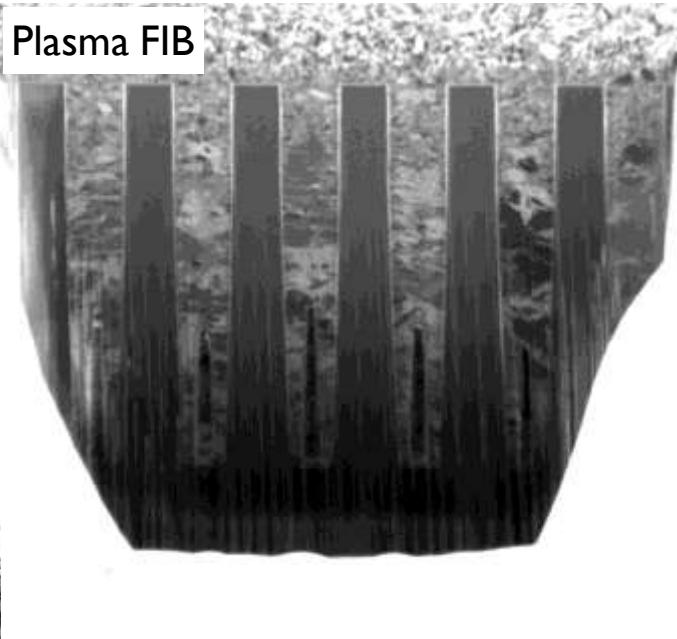
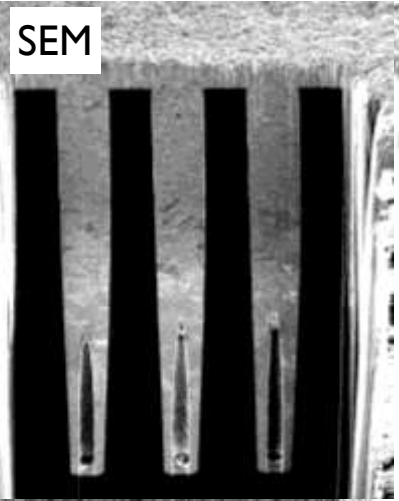


# MILL FROM SIDE



# Xe PLASMA FIB

Demo results  
No system available !  
Also : single beam



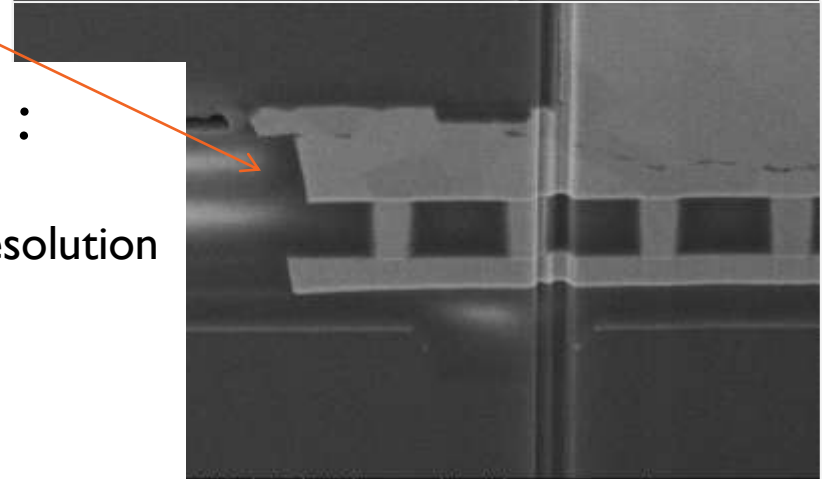
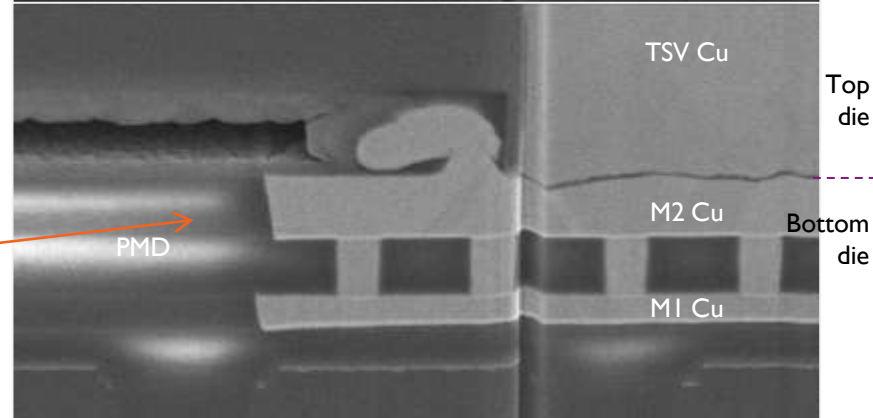
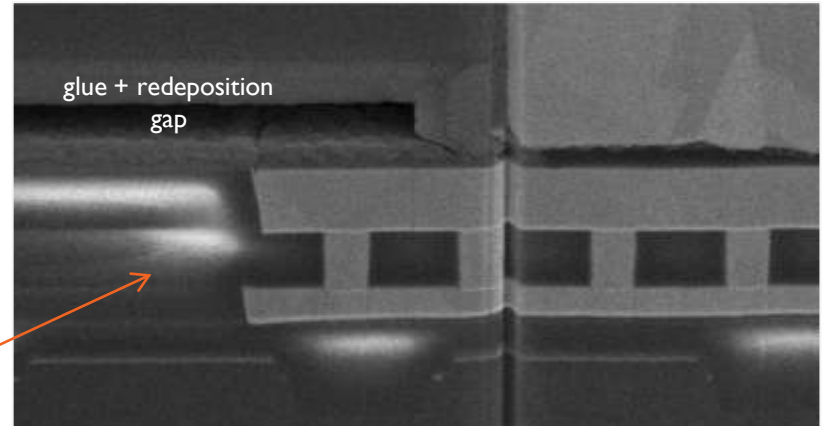
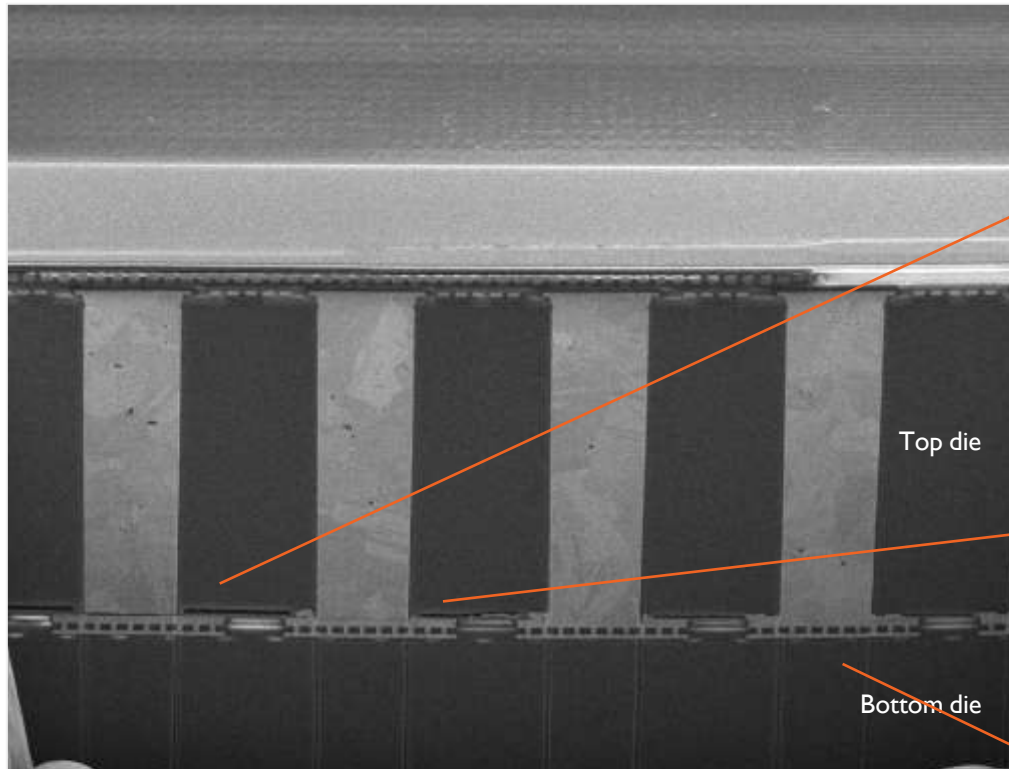
IMEC

Oregon Physics  
Noel Smith

FEI  
Ruud Schampers

Ga-FIB 20-40 nA → Xe-plasma source >500-1000 nA

# BONDED DIES



## Interests :

- **bonding quality**
- Cu filling (voids)
- grain size
- barrier
- oxide liner

imec

© IMEC 2010

## Analysis challenges :

- **no cleaving possible**
- dimensions vs required resolution
- depth of focus
- 3D analysis
- curtaining
- analysis time

HV det tilt mag dwell  
3.00 kV TLD 52° 50 000 x 60 µs  
1 µm  
MSN13



# TSV OPTIONS FOR CROSS-SECTIONAL INSPECTION

	Embed & polish	Standard DB-FIB mill	Cleave & DB-FIB mill	Mill from the side	Plasma-FIB
Speed	Slow	Slow	Medium	Medium	Fast
Typical for 50 $\mu\text{m}$ TSV	8 h	6-8 h	3-4 h	3-4 h	1 h
Area	Large	>30x50 $\mu\text{m}^2$	>30x50 $\mu\text{m}^2$	>50x10 $\mu\text{m}^2$	>100x100 $\mu\text{m}^2$
Quality	Polishing artefacts Void filling	SEM for voids FIB for grains Curtaining	SEM for voids FIB for grains Curtaining	SEM for voids FIB for grains Less curtaining	FIB only Curtaining
3D	~	Slice and view	Slice and view	Slice and view	Slice and tilt
Bonded dies	(Yes)	Yes	No	No	Yes
Difficulty	Patient operator	Mature	Mature	Mature	System in development

# CONCLUSION

- ▶ 3D-FIB on large structures is very time consuming
- ▶ Cleaving reduces time (if possible, but still >4h)
- ▶ Automated slice&view has problem of resolution vs total overview (no simple intermediate zooming possible)
- ▶ Manual slice and view generally needed (actually always applied)
- ▶ Outlook / dreams
  - Higher beam current FIB systems : will be mainly beneficial for the large volume milling
  - Higher milling rates : higher energy ? Other beams ?
  - Plasma-FIB : unclear when it will become available

A large, abstract graphic of purple smoke or ink swirling downwards from the top left corner of the page.

**ASPIRE  
INVENT  
ACHIEVE**

Acknowledgement  
Demo's : Oregon Physics, FEI, Hitachi

